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# LIFT – SYSTEM SETUP

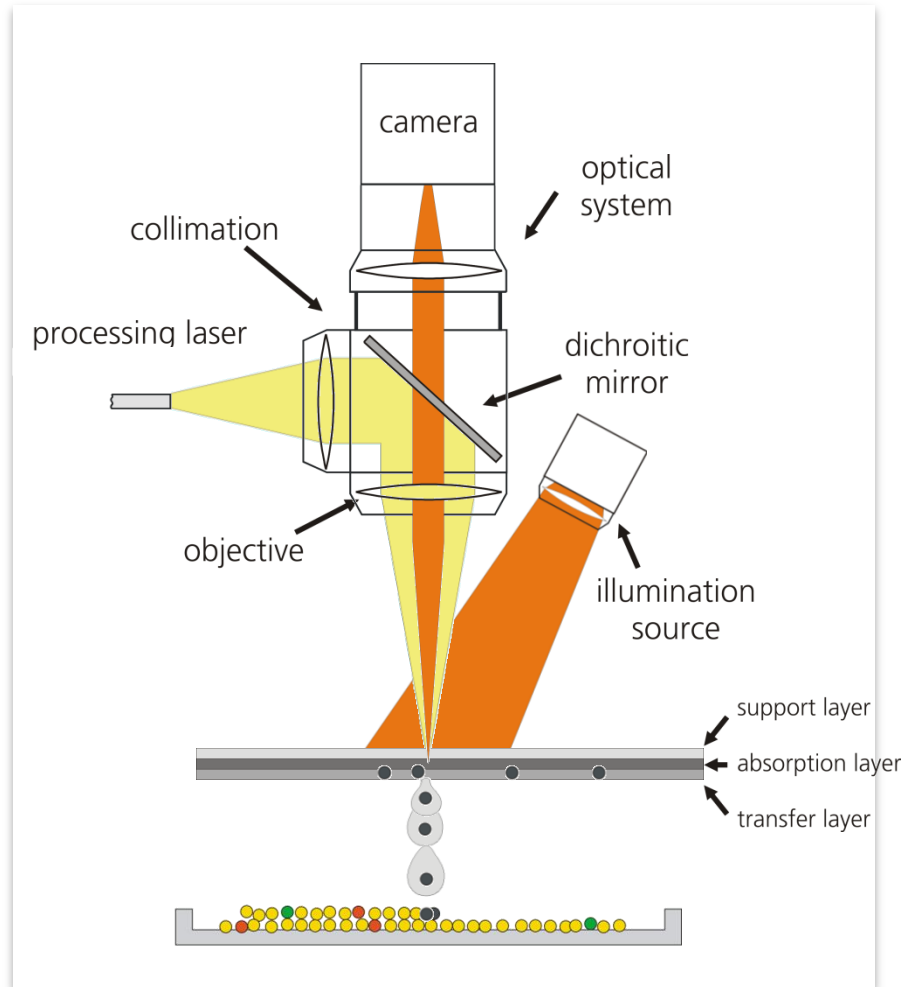
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Dr.-Ing. Martin Wehner,  
Tel.: 0241 8906-202,  
[martin.wehner@ilt.fraunhofer.de](mailto:martin.wehner@ilt.fraunhofer.de)

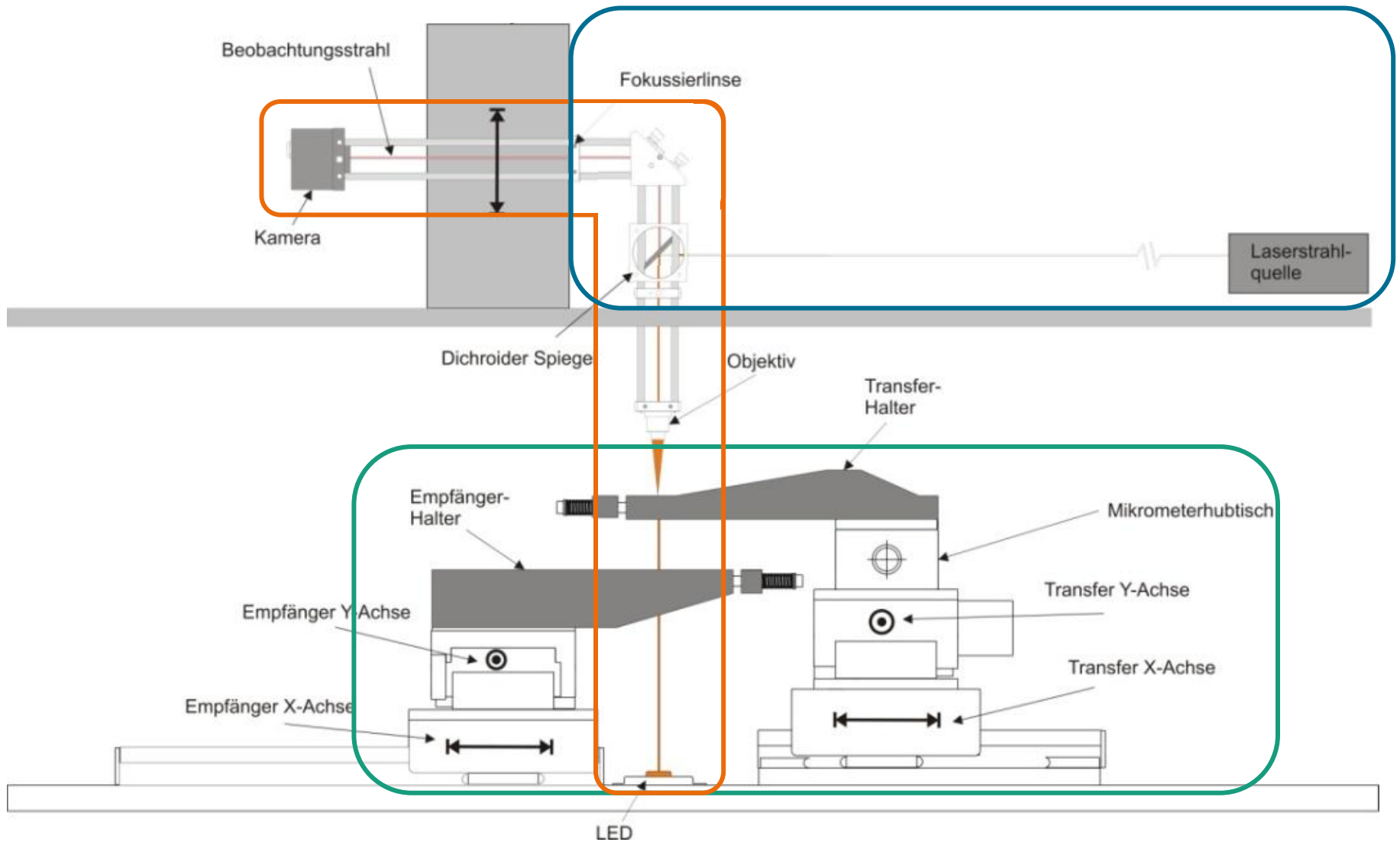
Dominik Riester,  
Tel.: 0241 8906-529,  
[dominik.riester@ilt.fraunhofer.de](mailto:dominik.riester@ilt.fraunhofer.de)

# Laser Induced Forward Transfer (LIFT)



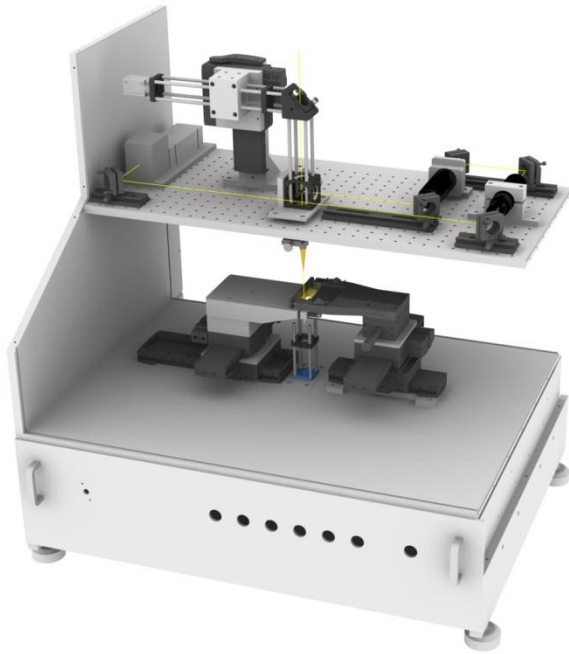
- Transfer slide with absorbance layer (Ti, Au etc.)
- Thin absorber layer (60 – 100 nm)
- Distance between transfer and receiver slide : 100  $\mu\text{m}$  – 2 mm
- Arbitrary patterning possible
  
- Laser source: pulsed Laser (e.g. microchip Laser, 1064 nm or 355 nm, pulse width 1 ns)

# LIFT concept

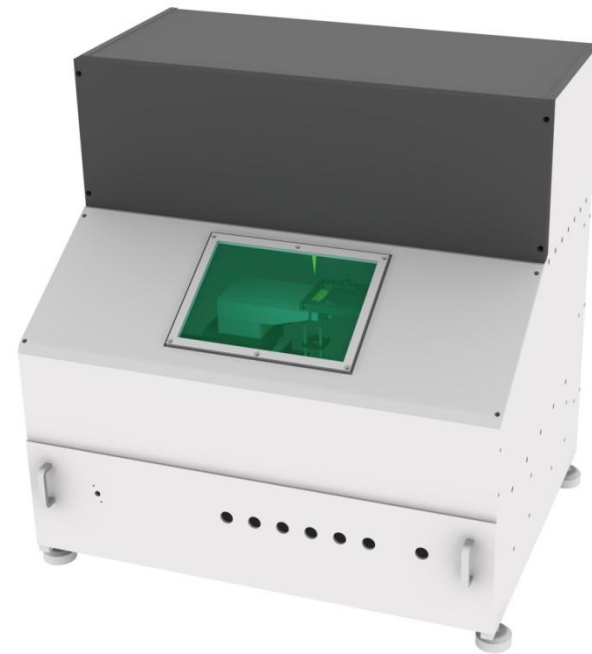


# LIFT System (Size: 800 x 500 x 700 mm<sup>3</sup>)

View of Laser compartment and process chamber



Tool in housing



# LIFT System (demonstrator) I



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# LIFT System (demonstrator) I I

